

**RESPONSE UNDER 37 CFR §1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 1794**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of Atty. Docket : NL 021426

RALPH KURT ET AL. Group Art Unit: 1794

Serial No. 10/539,362 Examiner: ELIZABETH E. MULVANEY

Filed: JUNE 15, 2005 CONF. NO. 7350

**TITLE: USE OF BI-LAYER PHOTOLITHOGRAPHIC RESISTS AS NEW MATERIAL  
FOR OPTICAL STORAGE**

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. §1.116

Sir:

In response to the Final Office Action of July 25, 2008,  
please amend the application and consider the remarks as follows: